

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	355	ozone same (half\$1life)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 16:32
S4	96	(makoto near2 takemura). in.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 09:20
S5	50	(yasuo near2 fukuda).in.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 09:20
S6	2	(kazuaki near2 souda).in.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 09:21
S7	115	(masaaki near2 kato).in.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 09:21
S8	2	(eiji near2 suhara).in.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 09:21
S9	269	510/175.ccls. and (ozone)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 10:31
S10	137	S9 and (ethanol or (isopropyl near2 alcohol) or IPA)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 10:31
S11	853	(clean\$3 with (substrate or wafer or semiconductor)) same (ozone and (ethanol or isopropanol or (isopropyl near2 alcohol) or IPA))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 10:34
S12	1	ozone with (suppress\$3) with reduct\$4 with (half \$1life)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 10:36
S13	72	(clean\$3 with (substrate or wafer or semiconductor)) same (ozone and (ethanol or isopropanol or (isopropyl near2 alcohol) or IPA))	EPO; JPO; DERWENT	OR	ON	2008/12/10 10:36
S14	951	(clean\$3 with (substrate or wafer or semiconductor)) and ((ultra\$1pure or (de \$1ionized near2 water)) and ozone and (ethanol or isopropanol or (isopropyl near2 alcohol) or IPA))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 10:38

S15	173	(clean\$3 with (substrate or wafer or semiconductor)) same ((ultra\$1pure or (de \$1ionized near2 water)) and ozone and (ethanol or isopropanol or (isopropyl near2 alcohol) or IPA))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 10:38
S16	102	(clean\$3 with (substrate or wafer or semiconductor)) same ((ultra\$1pure or (de \$1ionized near2 water)) same ozone same (ethanol or isopropanol or (isopropyl near2 alcohol) or IPA))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 10:43
S17	91	510/175.ccls. and (ozone) and (ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA) and ((pure near2 water) or (de\$1ionized near2 water))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 12:20
S18	3	510/175.ccls. and ((ozone) same (ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA) same ((pure near2 water) or (de\$1ionized near2 water)))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 12:36
S19	4	"510"/\$.ccls. and ((ozone) same (ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA) same ((pure near2 water) or (de\$1ionized near2 water)))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 12:37
S20	255	(clean\$3 with (substrate or wafer or semiconductor)) and ((ozone) same (ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA) same ((pure near2 water) or (de\$1ionized near2 water)))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 12:42

S21	22	(clean\$3 with (substrate or wafer or semiconductor)) and ((ozone) same (ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA) same ((pure near2 water) or (de\$1ionized near2 water)))	EPO; JPO; DERWENT	OR	ON	2008/12/10 12:42
S22	902	((add\$3 or supply\$3 or mix\$3) with (ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA) with (water)) same (membrane)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 12:55
S23	414	S22 and (wafer or substrate or semiconductor)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 12:58
S24	56	S22 and (electrolytic)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 12:59
S25	28	S23 and (electrolytic)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 12:59
S26	0	((add\$3 or supply\$3 or mix\$3) with (ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA) with (water) with ozone) same (membrane)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 13:07
S27	10	((add\$3 or supply\$3 or mix\$3) same (ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA) same (water) same ozone) same (membrane)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 13:07
S28	1	("6200387").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/12/10 13:41
S29	404	(generat\$3 with ozone) same (silent near2 discharge)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 15:30
S30	316	(generat\$3 with ozone) with (silent near2 discharge)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 15:30
S31	58	S30 and (clean\$3 with (substrate or wafer or semiconductor))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 15:31

S32	10	S31 and ((organic near2 solvent) or (ethyl near2 alcohol) or ethanol or (isopropyl near2 alcohol) or isopropanol or IPA)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 15:35
S33	2	((generat\$3 with ozone) with (silent near2 discharge)) same ((organic near2 solvent) or (ethyl near2 alcohol) or ethanol or (isopropyl near2 alcohol) or isopropanol or IPA)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 15:37
S34	0	JP-11-029795-\$.did.	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2008/12/10 16:04
S35	0	JP-1999-029795-\$.did.	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2008/12/10 16:04
S36	0	JP-1999029795-\$.did.	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2008/12/10 16:04
S37	1	JP-11029795-\$.did.	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2008/12/10 16:04
S38	1	JP-2000147793-\$.did.	US-PGPUB; USPAT; USOCR; DERWENT	OR	ON	2008/12/10 16:06
S39	13	510/175,176.ccls. and ((ozone near2 water) or (ozonated near2 water)) and (IPA or isopropanol or (isopropyl near2 alcohol))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 16:09
S41	119	"438"/\$.ccls. and ((ozone near2 water) or (ozonated near2 water)) and (IPA or isopropanol or (isopropyl near2 alcohol))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 16:10
S42	118	S41 and (substrate or wafer or semiconductor)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 16:10
S43	3	((("6699330") or ("6167583") or ("6230720"))).PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/12/10 16:11

S44	105	"134"/1.3,2,26,42.ccls. and ((ozone near2 water) or (ozonated near2 water)) and (IPA or isopropanol or (isopropyl near2 alcohol))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 16:13
S45	203	"134"/\$.ccls. and ((ozone near2 water) or (ozonated near2 water)) and (IPA or isopropanol or (isopropyl near2 alcohol))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 16:14
S46	203	S45 and (substrate or wafer or semiconductor)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/10 16:14
S47	1	("6517999").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/12/11 08:57
S48	203	"134"/\$.ccls. and ((ozone near2 water) or (ozonated near2 water)) and (IPA or isopropanol or (isopropyl near2 alcohol))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/11 10:41
S49	41	"134"/\$.ccls. and (((ozone near2 water) or (ozonated near2 water)) with (IPA or isopropanol or (isopropyl near2 alcohol)) or (ozone with ((pure near2 water) or (de \$1ionized near2 water)) with (ethanol or (ethyl near2 alcohol) or IPA or isopropanol or (isopropyl near2 alcohol))))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/11 10:43
S50	160	(clean\$3 with (substrate or wafer or semiconductor)) and (((ozone near2 water) or (ozonated near2 water)) with (IPA or isopropanol or (isopropyl near2 alcohol)) or (ozone with ((pure near2 water) or (de \$1ionized near2 water)) with (ethanol or (ethyl near2 alcohol) or IPA or isopropanol or (isopropyl near2 alcohol))))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/11 10:43
S51	0	(PURETRON).as. and (organic with (g/liter))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/11 12:04
S52	2	(sumitomo).as. and (organic with (g/liter))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/11 12:04

S53	1	(echo).as. and (organic with (g/liter))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/11 12:04
S54	0	(chlorine).as. and (organic with (g/liter))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/11 12:05
S55	0	(chlorine near2 engineers).as. and (organic with (g/liter))	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/11 12:05
S56	0	(PURETRON).as. and (organic with (g/liter))	EPO; JPO; DERWENT	OR	ON	2008/12/11 12:05
S57	0	(sumitomo).as. and (organic with (g/liter))	EPO; JPO; DERWENT	OR	ON	2008/12/11 12:05
S58	0	(echo).as. and (organic with (g/liter))	EPO; JPO; DERWENT	OR	ON	2008/12/11 12:05
S59	0	(chlorine).as. and (organic with (g/liter))	EPO; JPO; DERWENT	OR	ON	2008/12/11 12:05
S60	2	((add\$3 or supply\$3 or mix\$3) with (solvent or ethanol or (ethyl near2 alcohol) or isopropanol or (isopropyl near2 alcohol) or IPA)) same (membrane) same (ozone near2 water)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:12
S61	24	Bran.in. and 134/902.ccls.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:41
S62	174	porous and 134/902.ccls.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:44
S63	25	(porous with gas) and 134/902.ccls.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:44
S64	142	markoff and 134/902.ccls.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:45
S65	27	S64 and (porous or membrane)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:45
S66	174	markoff and (porous or membrane)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:46
S67	63	markoff and (porous or membrane) and "134"/\$.ccls.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:48
S68	293	(porous or membrane) and "134"/902.ccls.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 13:51
S69	1	("5014727").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/12/12 14:03
S70	53	("2541838" "3396950" "4288394").PN. OR ("5014727").URPN.	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 14:03

S71	22	Markoff and (CO2 or "CO. sub.2" or (carbon near2 dioxide)) and (ozone or ozonation or ozon\$5)	US-PGPUB; USPAT; USOCR	OR	ON	2008/12/12 14:20
S72	1	("5723173").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2008/12/12 14:59

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